Schedule of Accreditation

issued by

United Kingdom Accreditation Service

2 Pine Trees, Chertsey Lane, Staines-upon-Thames, TW18 3HR, UK

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Accredited to ISO/IEC 17025:2005

University of Surrey, Ion Beam Centre

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Calibration performed at the above address only

DETAIL OF ACCREDITATION

Measured Quantity Instrument or Gauge	Range	Calibration and Measurement Capability (CMC) Expressed as an Expanded Uncertainty (k = 2)	Remarks
Retained ion dose (quantity of material)	Ion implantation in silicon: 10^{15}/cm^2 of arsenic implanted at 150 keV, or similar implants whose spectrometry signals are comparable	2.0%	Rutherford Backscattering Spectrometry (RBS) using a 2 MV tandem accelerator. Silicon surface must be fully amorphised to a depth of about 100 nm
END			